

## Electronic Patent Application Fee Transmittal

Application Number:	10578683
Filing Date:	09-May-2006
Title of Invention:	FABRICATION METHOD OF EXTREME ULTRAVIOLET RADIATION MASK MIRROR USING ATOMIC FORCE MICROSCOPE LITHOGRAPHY
First Named Inventor/Applicant Name:	Hai Won Lee
Filer:	Rebecca Mather McNeill/Jennifer Arguelles
Attorney Docket Number:	05823.0283

Filed as Small Entity

### **U.S. National Stage under 35 USC 371 Filing Fees**

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
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**Basic Filing:**

**Pages:**

**Claims:**

**Miscellaneous-Filing:**

**Petition:**

**Patent-Appeals-and-Interference:**

**Post-Allowance-and-Post-Issuance:**

Utility Appl issue fee	2501	1	755	755
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Extension-of-Time:</b>				
<b>Miscellaneous:</b>				
<b>Total in USD (\$)</b>				<b>1055</b>